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## (54) PHOTOSENSITIVE RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a negative photosensitive resin composition applicable to manufacture semiconductor elements and circuit boards and the like and high in sensitivity and resolution and superior in heat resistance by incorporating a polyamic acid or polyimide each having cis-diene structures on the side chains and an oxygen sensitizing dye.

SOLUTION: This photosensitive resin composition contains a oxygen sensitizer and polyamic acid or polyimide each substituted by the cis-diene structures represented by the formula in which at least one of R1-R4 is a monovalent organic group having the cis-diene structure and each of the others is, independently, an H atom or a hydroxyl or carboxyl or 1-20C alkyl or such alkoxy group. The cis-diene structure is a furan or thiophene or pyrrole, and the oxygene sensitizer is a flarene compound and the structural units of the formula amount to ≥30 mol. % of the total diamine structural units, thus the resin layer to be enhanced in sensitivity and resolution and heat resistance is obtained.

$$= N - R^{1} - R^{2}$$

$$= R^{2} - R^{3}$$

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